

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Hisami BESSHO et al.

Group Art Unit: 2871

Application No.: 10/593,622

Filed: September 21, 2006

Docket No.: 129521

For: ANISOTROPIC CONDUCTIVE FILM AND A METHOD OF MANUFACTURING THE SAME

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR §1.56, the attention of the Patent and Trademark Office is hereby directed to the reference(s) listed on the attached PTO-1449. Unless otherwise indicated herein, one copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the reference(s) be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

- ☒ 1. This Information Disclosure Statement is being filed (a) within three months of the U.S. filing date of this non-CPA application, OR (b) before the mailing date of a first Office Action on the merits in the present application. No certification or fee is required.
- ☒ 2. Relevance of one or more non-English language reference is discussed in the present specification. See References 1, 2 and 7 - 9.
- ☒ 3. One or more reference cited herein was cited in the International Search Report. A copy of the International Search Report is attached for the Examiner's information. See References 1 - 6.
- ☒ 4. An English language Abstract of one or more non-English language reference is attached hereto. See References 1 - 4 and 6.
- ☒ 5. A computer-generated English language translation of one or more Japanese Patent Publication cited herein has been obtained from the website of the Japanese Patent Office ([<http://www.jpo.go.jp>]), and is attached, but has not been reviewed for accuracy. See References 1 - 4 and 6.

- ☒ 6. A partial English language translation of the relevant parts of one or more Japanese non-patent publication cited herein is attached, but has not been reviewed for accuracy. See References 7 and 8.

Respectfully submitted,



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Form PTO-1449 (REV. 1/06)		US Dept. of Commerce PATENT & TRADEMARK OFFICE		ATTY DOCKET NO. 129521		APPLICATION NO. 10/593,622	
INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)				APPLICANT(S) Hisami BESSHO et al.			
				FILING DATE September 21, 2006		GROUP 2871	
U.S. PATENT DOCUMENTS							
Examiner Initials	Cite No.	Document Number	Date	Name			
FOREIGN PATENT DOCUMENTS							
Examiner Initials	Cite No.	Document Number	Date	Country	With English Abstract	With English Translation	
	1	JP A 8-273442	10/18/1996	JAPAN	X	X	
	2	JP A 2003-80538	03/19/2003	JAPAN	X	X	
	3	JP A 2001-30264	02/06/2001	JAPAN	X	X	
	4	JP A 6-283225	10/07/1994	JAPAN	X	X	
	5	JP A 62-229713	10/08/1987	JAPAN			
	6	JP A 2002-327155	11/15/2002	JAPAN	X	X	
OTHER DOCUMENTS							
Examiner Initials	Cite No.	(Including Author, Title, Date, Pertinent Pages, etc.)					
	7	Shimomura, Masatsugu. "Formation and Functionalization of Nano/Meso Hole Structures by Self-Organization of Polymer Materials," <i>Functional Materials</i> , CMC Publishing Co., Vol. 23, No. 10, pp. 18 - 26, October 2003.					
	8	Shimomura, Masatsugu. "Pattern-Forming by Self-Organization and its Application to Microprocessing Techniques," <i>Materia</i> , the Japan Institute of Metals, Vol. 42, No. 6, pp. 457 - 460, 2003.					
	9	Takeichi, Mothide. "Flip-Chip Mounting Techniques Using Anisotropic Conductive Films," <i>Electronic Materials</i> , Kogyo Chosakai Publishing Co., Appendix, pp. 130 - 133, May 2001.					
EXAMINER					DATE CONSIDERED		
Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							

Date: December 15, 2006